

1 Analyses of Size and Morphology of Nanoparticles by Atomic Force Microscope <GI-9-182>

4 (原子間力顕微鏡によるナノ粒子のサイズ及び形態解析法 <GI-9-182>)

7 Atomic Force Microscopy (AFM) is a technique to analyze
8 the size, morphology, and surface shape of nanoparticles with
9 the images captured by detecting the atomic force between a
10 sample surface and a tiny probe tip with a curvature radius in
11 the order of nanometers (Fig. 1) mounted on a cantilever. It
12 can be performed in air or liquid. Mechanical attributes of
13 nanoparticles such as stiffness can also be determined as well.
14 AFM has been used for the characterization of pharmaceuticals
15 based on nanotechnology.

16 1. Equipment and operating principle

17 1.1. AFM system

18 The AFM system consists of a semiconductor laser, an
19 AFM head (the component part of the instrument that a can-
20 tilever is mounted on), a cantilever with a probe tip, a sample
21 stage, and a split photodiode, etc. and is equipped with an
22 optical microscope and a CCD camera to properly align the
23 laser beam irradiated at the cantilever (Fig. 1). The AFM sys-
24 tem is placed on a vibration-isolation table to prevent any vi-
25 bration that may affect the measurement.

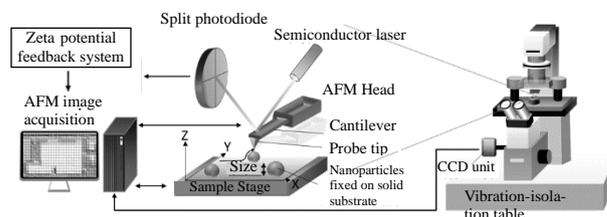
26 1.2. AFM operating principle

27 The operating principle of AFM is generally described as
28 follows (Fig. 1).

- 29 1) A semiconductor laser is irradiated to the back of the
30 cantilever and the reflected laser beam is constantly
31 monitored at the split photodiode.
- 32 2) As the cantilever approaches the vicinity of a sample
33 surface, the cantilever deflects in response to the bend-
34 ing moment generated by the intersurface force (attrac-
35 tive or repulsive). The deflection is measured as upward
36 or downward displacement of the laser detection posi-
37 tion at the split photodiode.
- 38 3) For the deflection of the cantilever to remain constant,
39 while the distance in the z-axis direction between the
40 cantilever and the sample surface is controlled by a pie-
41 zoelectric drive attached to the sample stage or AFM
42 head, the cantilever is scanned in the directions of x and
43 y directions of the sample.

44 Based on the operating principle as 1) ~3) above, an AFM
45 image is captured with the height information recorded per
46 pixel. In actual image acquisition, the nanoparticles to be
47 measured are fixed onto a flat solid substrate and the height
48 of the particles is measured from the substrate surface. In
49 measuring the size of nanoparticles, assuming that the object
50 nanoparticles are spherical, the height measured by AFM is

51 equivalent to the particle size. By further using a standard
52 sample for calibration, the height in the z-axis direction in
53 AFM images can be highly accurate and precise. On the other
54 hand, information on the lateral (x, y) dimension obtained
55 with AFM images needs to consider the difficulty of calibra-
56 tion and the influence of the geometry of the probe tip.



57 **Fig. 1.** Schematic diagram of a typical atomic
58 force microscope system and PC for image ac-
59 quisition¹⁾

59 1.3. Other equipment

60 Acoustic enclosure: An acoustic wall box may be used to
61 house the AFM system, to protect from vibration that may be
62 caused by external sound.

63 UV cleaning system: This is used to clean the cantilever.

64 Temperature control system: This is used when samples
65 need to be measured at a constant temperature.

66 2. Measurement

67 Measurement of the size of nanoparticles using AFM is
68 generally performed in the following procedure.

69 2.1. Preparation of samples

70 Samples are prepared by dispersing the object nanoparti-
71 cles in a suitable solvent at an appropriate concentration. The
72 solvent and concentration are selected so as to maintain the
73 stable dispersion of the nanoparticles.

74 2.2. Preparation of substrate for fixing nanoparticles

75 Fixing the sample to be observed onto a solid substrate is
76 essential for acquiring AFM images. To select an appropriate
77 substrate based on physicochemical properties of the sample
78 to be observed is an important element in studying for the
79 optimal conditions such as the number of the observed parti-
80 cles and the morphology.

81 To make sure a stable baseline for measuring the height,
82 the substrate surface roughness needs to be sufficiently flat
83 compared to the particles to be measured. The surface rough-
84 ness (arithmetic mean roughness, which is the average of the
85 absolute values of deviations from the center line for bumps
86 and dips of the surface) is desirable not more than 5% of the
87 size of the particles to be measured. It is also important that
88 the physical properties of the substrate surface are relatively
89 uniform for fixing nanoparticles easily.

90 In general, the surfaces of nanoparticles in a stable disper-
91 sion state are either positively or negatively charged, and the
92 fixation of the nanoparticles onto a solid substrate is often

93 made by electrostatic interaction. Negatively charged poly-
 94 styrene standard nanoparticles, for example, can be easily
 95 fixed onto a positively charged solid substrate surface. A
 96 number of studies are required for selecting an appropriate
 97 solid substrate, particularly when the interactions are com-
 98 plex such that surface forces between a particles and a sub-
 99 strate depend on van der Waals or hydrophobic interactions,
 100 or such that due to the interaction with a substrate deforma-
 101 tion or disintegration occur on the soft particles to be fixed.
 102 A high-quality mica (muscovite mica), gold (111) -vapor
 103 fixed mica and single crystal silicon are commercially avail-
 104 able representative substrates for AFM measurement. These
 105 substrates have atomically flat surfaces and can be surface-
 106 treated for controlling the electronic charge state of the sub-
 107 strate surface. For instance, to fix negatively charged nano-
 108 particles, 0.3 vol % of 3-aminopropyltriethoxysilane
 109 (APTES) aqueous solution can be used to treat the surface for
 110 a positive charge. Relatively flat cover glass with surface
 111 roughness of approximately not more than 5 nm is commer-
 112 cially available, which may be used as a substrate for parti-
 113 cles with the size of approximately not less than 100 nm. It is
 114 desirable to acquire AFM images of the substrate in advance
 115 to get the information on the surface roughness of the sub-
 116 strate to be used.

117 2.3. Nanoparticle fixation on a solid substrate

118 Apply a liquid sample of nanoparticles onto a suitable sub-
 119 strate and incubate for a sufficient time to allow the particles
 120 fixed onto a substrate. When AFM images are acquired in air,
 121 after the incubation, rinse the substrate with ultrapure water
 122 to remove excess components such as salts and dry.

123 2.4. Acquisition of AFM images

124 2.4.1 Selection of measurement mode

125 Nanoparticles are fixed to a substrate by weak intermolec-
 126 ular interactions such as electrostatic interaction and van der
 127 Waals interaction. It is therefore important to minimize the
 128 force applied to the lateral dimension by an AFM measure-
 129 ment mode. One of the measurement modes to meet this re-
 130 quirement is the intermittent contact mode (also called dy-
 131 namic mode, tapping mode, dynamic force mode, or ampli-
 132 tude-modulated mode), which is available for most commer-
 133 cially available AFM equipment. In recent years, however,
 134 the nonresonant mode (force curve mapping) that does not
 135 vibrate a cantilever may be used in observing a particularly
 136 soft sample or in the measurement of mechanical properties
 137 (e.g., stiffness).

138 In the intermittent contact mode, the cantilever is oscillated
 139 up and down at a frequency close to the resonance frequency
 140 by a small piezoelectric element fit in the cantilever holder.
 141 The amplitude of the oscillation is very sensitive to the dis-
 142 tance between the probe tip and the sample, and the ampli-
 143 tude quickly becomes small upon the probe tip contacting the
 144 sample surface by dissipating the kinetic energy of the

145 cantilever toward the sample. With the distance between the
 146 probe tip and the sample being feed-back controlled to keep
 147 the oscillation amplitude constant, the particle surface in the
 148 sample is scanned by oscillating the cantilever up and down
 149 constantly, resulting in an advantage of almost nil force to-
 150 ward the lateral dimension. For this reason, this is a valid
 151 measurement mode also for those samples that move easily,
 152 have uneven surface, are soft or with adsorption to the surface.
 153 Size measurement of nanoparticles can be made in air or in
 154 liquid environments by the intermittent contact mode. How
 155 to acquire images by the intermittent contact mode is de-
 156 scribed in the following.

157 2.4.2. Selection of cantilever

158 The characteristics and geometry of the cantilever and the
 159 probe tip attached to its end are important factors that deter-
 160 mine the sensitivity and resolution of AFM. Points to con-
 161 sider are given in the following.

162 Images obtained by AFM include factors derived from
 163 both the probe tip shape and the shape of sample particles. In
 164 other words, the shape of the probe tip has no effect in meas-
 165 uring the height of a particle, while it has effect in displaying
 166 the shape in the x and y directions of the nanoparticle. There-
 167 fore, caution is required to deal with the information on the
 168 sizes of nanoparticles in the x and y directions. To minimize
 169 artifacts derived from the probe tip shape, use of a probe tip
 170 having the tip radius of not more than 10 nm is recommended.

171 Stable excitation oscillation of a cantilever is an important
 172 factor in imaging sample surfaces by the intermittent contact
 173 mode, and the use of a cantilever with large stiffness (a high
 174 spring constant) is desirable to overcome adhesive forces be-
 175 tween the probe tip and sample particles (e.g., capillary, van
 176 der Waals, and electrostatic forces). On the other hand, since
 177 particles may be deformed by the force upon contact with the
 178 cantilever, it is thus desirable to use a cantilever with small
 179 stiffness (a low spring constant) than that of the particles to
 180 be measured. A cantilever with a high resonance frequency
 181 may shorten the measurement time due to better scanning
 182 sensitivity, but caution is required for the damage to the par-
 183 ticles to be measured due to the large stiffness (spring con-
 184 stant) in general. In addition, a cantilever with different stiff-
 185 ness may have to be used depending on observation in air or
 186 in liquid. The cantilever to be used should be determined in
 187 consideration of these points and should be optimized as re-
 188 quired.

189 2.4.3. Acquiring AFM images

190 A prepared sample is placed on the sample stage, and an
 191 AFM image is acquired. The AFM image has information on
 192 the x - y plane coordinates and the vertical z coordinates. The
 193 number of the data points in the x - y plane, or the pixel number,
 194 must be considered, when acquiring and analyzing the image.
 195 For example, a $10\ \mu\text{m} \times 10\ \mu\text{m}$ image with 200 pixels on a
 196 side acquired gives the size per pixel of $50\ \text{nm} \times 50\ \text{nm}$.

197 With this setting condition, particles smaller than 50 nm are
198 not discriminable. The scan size should therefore be set for
199 the size of the particles to be measured. Generally, it is desir-
200 able to set a scan size to be 10 pixels or more per particle in
201 the measurement. In the analysis of the average particle size
202 and particle size distribution by AFM, assuring a random
203 sampling of representative particles plays an important role.
204 Generally, it is recommended to measure the size of at least
205 100 or so nanoparticles and to acquire images from different
206 fields to avoid artificiality in measurements due to a single
207 field of view. In the event of the image quality becoming sud-
208 denly deteriorated during the acquisition, the cantilever
209 should be cleaned or replaced as is often the cause that the
210 cantilever gets dirt or worn.

211 An AFM image should be acquired under the same opera-
212 tion conditions using a substrate without the test nanoparti-
213 cles fixed. This is to make sure that artifacts or foreign mat-
214 ters that may be misconstrued as the target nanoparticles are
215 not contaminated from the operating process or the substrate
216 itself.

217 **3. Image analysis and size (height) measurement of na-** 218 **nanoparticles**

219 Acquired AFM images are analyzed after correcting the tilt
220 of height on the images derived from the placement of the
221 sample or the thermal drift of the equipment, using the soft-
222 ware provided by the AFM equipment manufacturer (soft-
223 ware by other developers for AFM image analysis can be also
224 used as well). Essential operating procedure for data analysis
225 in the size measurement of nanoparticles is described here-
226 under.

227 **3.1 Size measurement by cross-sectional shape analysis**

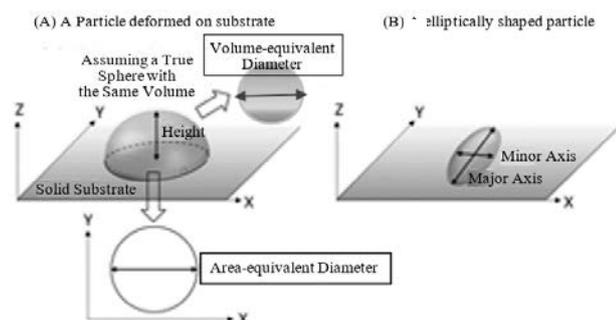
228 A cross-sectional shape profile in a vertical direction along
229 a line drawn across any part of an image is obtained using the
230 cross-sectional shape analysis tool of the software, thereby
231 making measurement of distance in horizontal and vertical
232 directions possible. With the cross-sectional shape profile, it
233 is possible to know the agglomerating property of nanoparti-
234 cles, as well as the height. The information can be obtained
235 on the appropriateness as to correcting the tilt of the substrate
236 around the nanoparticles. Cross-sectional shape analysis is
237 performed with respect to individual nanoparticles in the im-
238 age to measure the height. The benchmark for the height
239 measurement is the lowest point of all the data, the point
240 where geometry of the particle begins to rise in the scanning
241 direction, or the benchmark is set by the operator's discretion.
242 The series of measurement should be performed under the
243 same conditions regardless of the benchmark chosen. To
244 avoid influence of artifacts derived from the sample prepara-
245 tion, obvious foreign particles and large agglomerates that are
246 not individually distinguishable should be excluded in calcu-
247 lating the average particle size.

248 **3.2. Size measurement by automated particle analysis**

249 Software can be used to automatically identify particles
250 and enable the batch mode measurement of the particle size
251 in a short time. Particles are identified based on the threshold
252 of height set by users. That is, particles with a height equal to
253 or higher than the set threshold value are included in the anal-
254 ysis while those with a height lower than the set threshold
255 value are excluded. In addition, obvious foreign particles or
256 large agglomerates of indistinguishable particles are picked
257 up by the software and can be excluded from the analysis.
258 After the above operations, the maximum height of individ-
259 ual particles relative to the height of the substrate as the
260 benchmark is automatically measured. In the automated par-
261 ticle analysis, caution is required of artificial influence in the
262 results unless the tilt of the image to be analyzed is appropri-
263 ately corrected. When performing automated particle analy-
264 sis, the output of the results should be checked against the
265 results obtained by the cross-sectional shape analysis to con-
266 firm the validity of the results. The average height of nano-
267 particles by the automated analysis software tends to be
268 greater than the average height by the cross-sectional shape
269 analysis. In addition, some software analyzes particle size
270 based on the area occupied by individual particles in images.
271 In this case, the particle size is analyzed as an area-equivalent
272 diameter.

273 **3.3. Analysis of nanoparticles having shapes other than** 274 **true sphere**

275 When evaluating particle size, if particles are deformed
276 upon fixing the particles to a substrate or non-spheric parti-
277 cles are to be analyzed, it is important to consider that param-
278 eters other than the height are additionally analyzed using
279 particle analysis software. Where particles become deformed
280 upon fixation to a substrate, for example, the volume-equiv-
281 alent diameter may be used as a size evaluation parameter
282 (Fig. 2A), assuming that the volume is constant before and
283 after fixation to the substrate. In addition, it is also possible
284 to obtain information on the deformed shape of particles un-
285 der analysis based on the area-equivalent diameter, or the
286 height/area-equivalent diameter ratio (Fig. 2A). When the
287 particle under analysis is elliptically shaped, it is possible to
288 measure the length of the major and minor axes, assuming
289 that the particle corresponds to an ellipse, and is further pos-
290 sible to evaluate the shape based on the oblateness of the par-
291 ticle derived from the minor axis/major axis ratio (Fig. 2B).
292 In the analysis of non-sphere particles with additional infor-
293 mation on the lateral (x y) dimension, evaluate the tip shape
294 of the cantilever using a calibration grating to pay attention
295 because of the significant influence of the tip curvature.



296

297 **Fig. 2.** Geometry evaluation of a particle deformed on
a substrate (A) and an elliptically shaped particle (B)¹⁾

298 3.4. Reporting size data

299 The size (height) distribution and the average with the
300 standard deviation of nanoparticles measured should be re-
301 ported. The information on the method used to fix the parti-
302 cles, the cantilever, the measurement mode, whether the
303 measurement was made in air or in liquid, the number of the
304 nanoparticles measured, and the analysis method for size
305 should be described, as these factors involved in the meas-
306 urement have impact on the results of size measurement of
307 nanoparticles.

308 4. Verifying AFM performance

309 In AFM, the z -position of the cantilever is controlled for
310 the distance by the expansion and contraction of the piezoe-
311 lectric element. The expansion and contraction have proper-
312 ties such as non-linearity and hysteresis to the applied voltage.
313 The z -height is determined based on the voltage applied to
314 the piezoelectric element in conventional AFM. However,
315 due to the properties mentioned above, 'height correction'
316 based on a calibration curve prepared by measuring actual
317 samples with certified height should be required. For exam-
318 ple, selecting a calibration grating with a step height close to
319 the height of nanoparticles to be measured, the average of
320 step heights measured in at least three different locations us-
321 ing a sharp probe tip should be compared to the certified step
322 height of the calibration grating used.

323 If the average value measured is significantly different
324 from the certified value, it is necessary to consider the recal-
325 ibration of the z -displacement of the piezo drive device by
326 the manufacturer or others.

327 Some of recent AFM equipment is, on the other hand,
328 equipped with a length-measuring sensor attached to the pie-
329 zoelectric element and can precisely measure the degree of
330 expansion and contraction, thereby allowing constant meas-
331 urement of z -height. In other words, there exists the equip-
332 ment with a control method that correct the height or the dis-
333 placement.

334 References

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